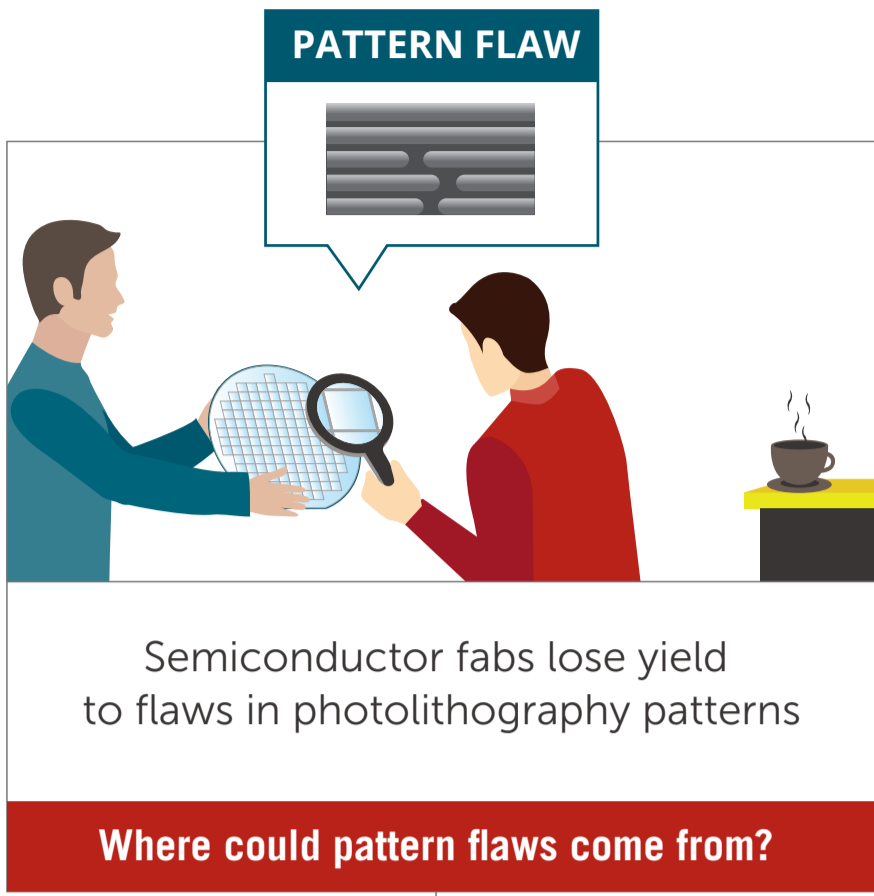
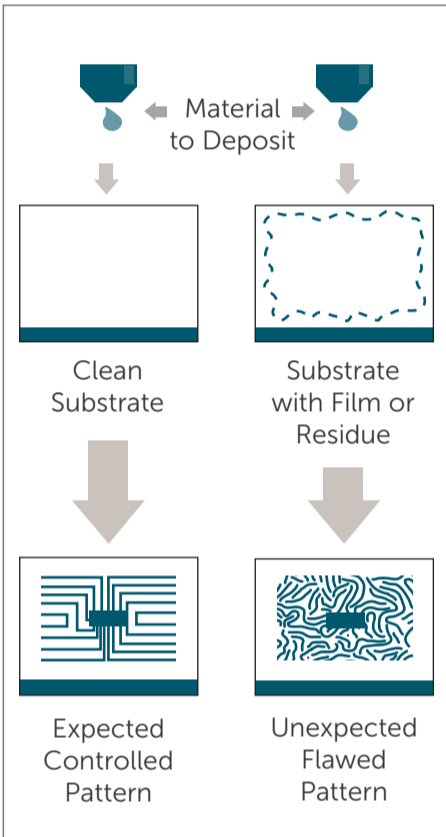


Chasing the Perfect Pattern

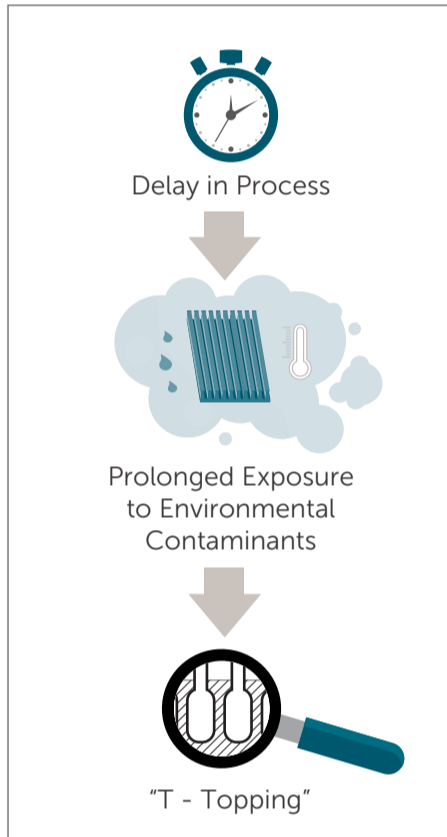
Flaws in photolithography patterns have always had a negative impact on yield. It is becoming more imperative than ever for semiconductor fabricators to prevent these pattern flaws. **Here's how they're doing it.**



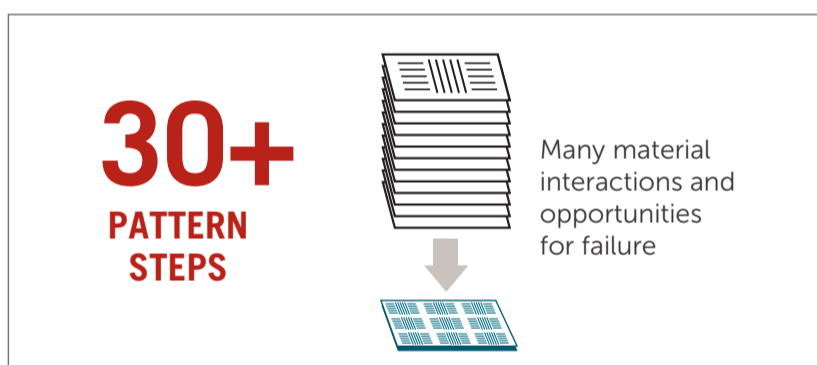
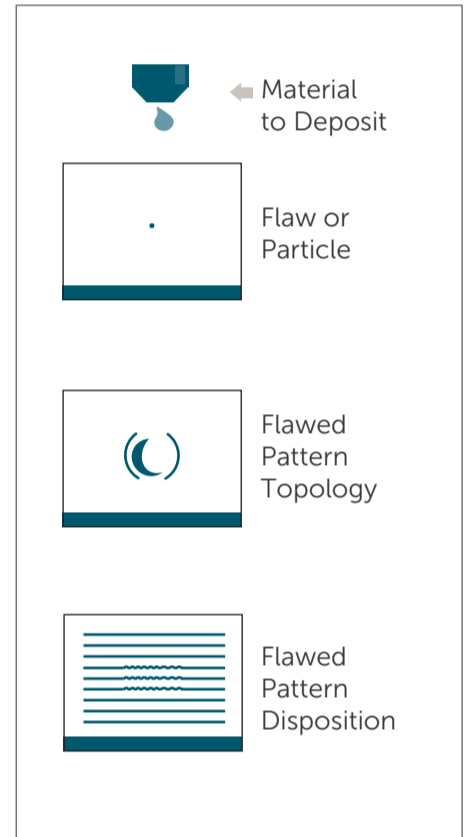
UNEXPECTED INTERACTION BETWEEN MATERIALS



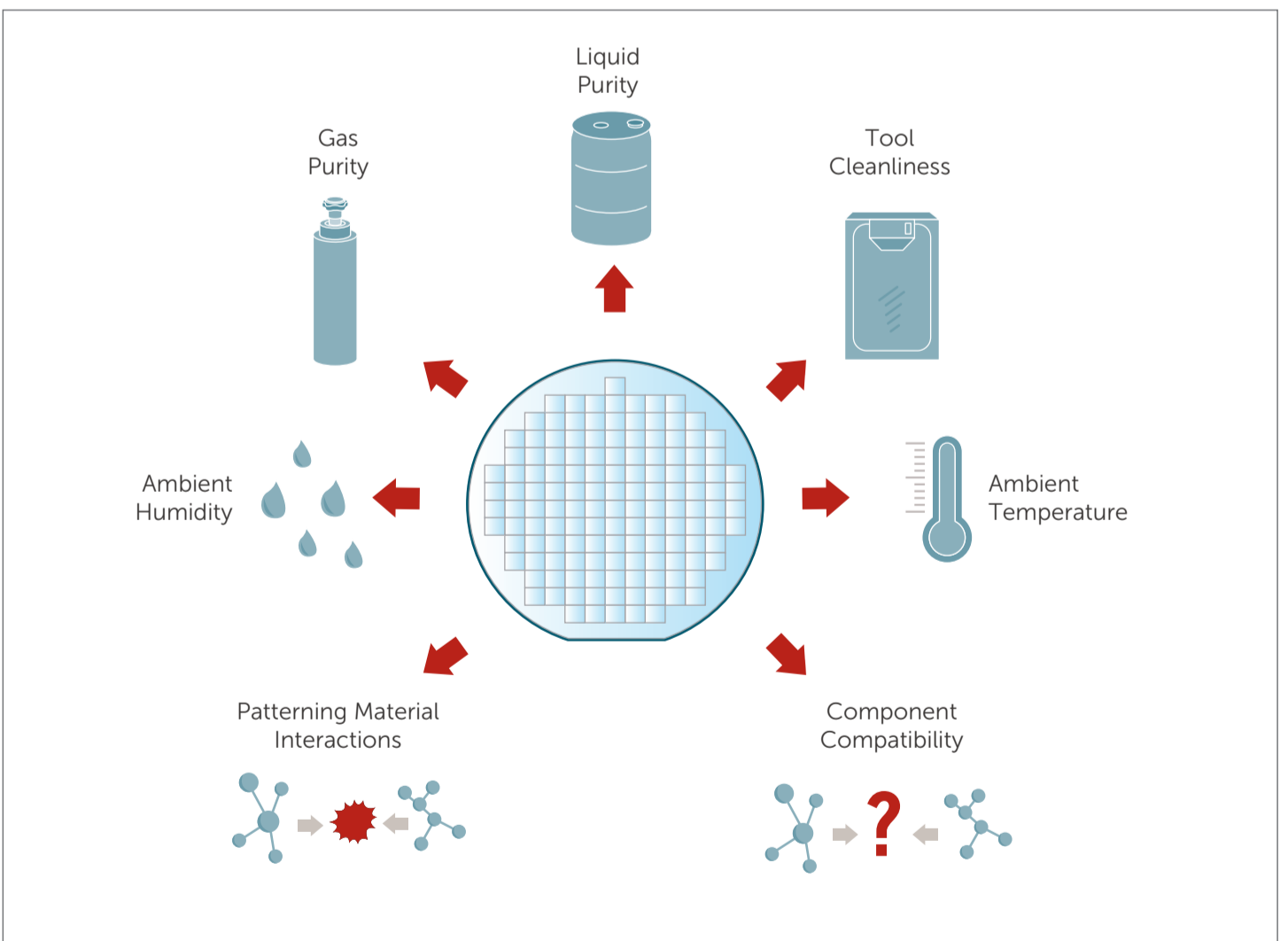
ATMOSPHERIC CONTAMINATION



"RIPPLE EFFECT" FROM A BURIED FLAW, AFFECTING SURFACE TOPOLOGY



FACTORS THAT CAN INFLUENCE PATTERNS



Managing filtration and purification to create the perfect pattern requires lithographers to explore emerging variables.

